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STATEMENT BY APPLICANT**
(Not for submission under 37 CFR 1.99)

Application Number	10518060
Filing Date	2005-06-09
First Named Inventor	Lutz Lehmann
Art Unit	1712
Examiner Name	Kua Liang Peng
Attorney Docket Number	H26787.68596 US - 4780

U.S.PATENTS

Examiner Initial*	Cite No	Patent Number	Kind Code ¹	Issue Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines where Relevant Passages or Relevant Figures Appear
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	2	4299938		1981-11-10	Ciba-Geigy Corporation	
	3	4349609		1982-09-14	Fujitsu Limited	
	4	4430153		1984-02-07	International Business Machines	
	5	4587138		1986-05-06	Intel Corporation	
	6	4863827		1989-09-05	American Hoechst Corporation	
	7	4910122		1999-03-20	Brewer Science, Inc.	
	8	4935583		1990-06-19	Kyle, James C.	

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22	5674648	A	1997-10-07	Brewer et al.	
23	4191571		1980-03-04	Nonogaki et al.	

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	1	20060110682	A1	2006-05-25	Shipley Company, L.L.C.	
	2	20060155594	A1	2006-07-13	Jess Almeida, et al.	

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	1	Crivello et al., J. Polym. Sci.: Polym. Chem. 21 (1983), 97-109.	<input type="checkbox"/>
	2	Degussa, "Silanes for Adhesives and Sealants," 18-19, available at www.dynasylan.com .	<input type="checkbox"/>
	3	Lamola, A. et al., "Chemically Amplified Resists," Solid State Technology, 53-60 (August 1991).	<input type="checkbox"/>
	4	Y.-C. Lin et al., "Some Aspects of Anti-Reflective Coating for Optical Lithography," Advances in Resist Technology and Processing, Proc., SPIE vol. 469, 30-37 (1984).	<input type="checkbox"/>
	5	McKean et al., "Characterization of a Novolac-Based Three-Component Deep-UV Resist," Chem. Mater. (1990) 2, 619-624.	<input type="checkbox"/>
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	7	Silverstein et al., "Spectrometric Identification of Organic Compounds," 4th Ed. John Wiley & Sons 1991, 309-311.	<input type="checkbox"/>
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	11	Jaskot et al., Toxicological Sciences, 22(1): 103-112 (1994). <input type="checkbox"/>
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	13	Brewer, T. et al., "The Reduction of the Standing Wave Effect in Positive Photoresists," Jour. Appl. Photogr. Eng., Vol. 7, no. 6, 184-186 (Dec. 1981). <input type="checkbox"/>
	14	Yusuke Izumi et al., "Hydrosilylation of Carbonyl Compounds Catalyzed by Solid Acids and Bases," Tetrahedron Letters, Vol. 32, No. 36, pp 4744 (1991). <input type="checkbox"/>

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